

200 PVD System

Design Intent:

The 200 PVD System is designed as a small, cost-effective system capable of depositing any number of coatings from a single cathodic-arc source. Due to the small footprint and low cost, this system is intended as a research and development system.

The 200 PVD System comes standard with a 5kW DC bias power supply, manual system controls, a 500 l/sec diffusion pump and a single, 63 mm diameter source. Complete specifications are shown below.

Capabilities:

This system can be used to deposit the following coatings with the appropriate source installed:

TiN, TiAlN, AlTiN, CrN and other nitrides. An extra gas control (optional) would provide carbide capabilities.

Optional equipment includes:

- Radiant heating of substrate
- Additional gas controls (carbides, etc.)
- Turbo pump
- Chamber shielding
- Fixturing

For more information, or to discuss the configuration best suited for you, please call Shannon Bosak at the number shown below, or email Shannon at:

sbosak@seggroupinc.net



200 PVD Coating System - Specifications

Chamber Size	200 mm Dia x 300 mm H
Chamber Construction	304 stainless steel, water cooled
Footprint	1m Wide x .75 m Deep
Deposition Source	1 Round, 63 mm Dia.
Substrate Bias	5 kW DC; 1250 V max.
Diffusion Pump	500 l/sec.
Mechanical Pump	15 l/sec.
System Controls	Manual
Gas Control	1 nitrogen mass flow controller
Substrate Temp. Monitor	1 infrared monitor
Coating Temperature	50°C to 500°C (125°F - 950°F)
Potential Coatings	TiN, CrN, TiAlN, other nitrides



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